

Title (en)

Lithographic apparatus and device manufacturing method

Title (de)

Lithografische Vorrichtung und Verfahren zur Herstellung einer Vorrichtung

Title (fr)

Appareil lithographique et procédé de fabrication d'un dispositif

Publication

EP 1826615 A2 20070829 (EN)

Application

EP 07075136 A 20070215

Priority

US 35872506 A 20060222

Abstract (en)

A lithographic apparatus includes a displacement measuring system to measure a position of a moveable object with respect to a reference frame of the lithographic apparatus, in at least three coplanar degrees of freedom (x,y,Rz) of an orthogonal x-y-z coordinate system centred in the center of the moveable object. The moveable object includes a support structure configured to support a patterning device or a substrate table (2) configured to support a substrate. The displacement measuring system includes at least three sensor heads (4,5,6,7), each sensor head being positioned with a measuring direction (54...57) substantially coplanar with the x-y plane of the coordinate system and each sensor head being furthermore positioned with the measuring direction substantially perpendicular to a connection line (10,11) connecting the sensor head with the center of the movable object and extending coplanar with the x-y plane.

IPC 8 full level

G03F 7/20 (2006.01)

CPC (source: EP KR US)

G03F 7/70725 (2013.01 - EP US); **G03F 7/70775** (2013.01 - EP KR US); **G03F 7/7085** (2013.01 - KR); **H01L 21/67259** (2013.01 - KR)

Citation (applicant)

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